–	3772	semiconductor and plasma and (recycle or recycling or re$1use or circulat$3 or (introduc$4 near3 again))	USPAT	2003/12/03 14:11
–	1515	(semiconductor and plasma and (recycle or recycling or re$1use or circulat$3 or (introduc$4 near3 again))) and (emission or (light near4 intensity) or emit or emitting)	USPAT	2003/12/03 14:18
–	1396	((semiconductor and plasma and (recycle or recycling or re$1use or circulat$3 or (introduc$4 near3 again))) and (emission or (light near4 intensity) or emit or emitting)) and @ay<=2000	USPAT	2003/12/03 14:13
–	487	(((semiconductor and plasma and (recycle or recycling or re$1use or circulat$3 or (introduc$4 near3 again))) and (emission or (light near4 intensity) or emit or emitting)) and @ay<=2000) and ((monitor$3 or analyz$3 or control$4 or obtain$3) with plasma)	USPAT	2003/12/03 14:18
–	1	6406924.pn.	USPAT	2003/12/03 15:10
–	343	((((semiconductor and plasma and (recycle or recycling or re$1use or circulat$3 or (introduc$4 near3 again))) and (emission or (light near4 intensity) or emit or emitting)) and @ay<=2000) and ((monitor$3 or analyz$3 or control$4 or obtain$3) with plasma)) and (etch or etching)	USPAT	2003/12/03 14:22
~	239	((((semiconductor and plasma and (recycle or recycling or re$1use or circulat$3 or (introduc$4 near3 again))) and (emission or (light near4 intensity) or emit or emitting)) and @ay<=2000) and ((monitor$3 or analyz$3 or control$4 or obtain$3) with plasma)) and (etch or etching)) and (intensity or amplitude or magnitude)	USPAT	2003/12/03 14:22
–	193	(((((semiconductor and plasma and (recycle or recycling or re$1use or circulat$3 or (introduc$4 near3 again))) and (emission or (light near4 intensity) or emit or emitting)) and @ay<=2000) and ((monitor$3 or analyz$3 or control$4 or obtain$3) with plasma)) and (etch or etching)) and intensity	USPAT	2003/12/03 14:23
–	1	5728253.pn.	USPAT	2003/12/04 10:13
–	1	6599842.pn.	USPAT	2003/12/03 16:22
–	1	5565114.pn.	USPAT	2003/12/03 16:22

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L Number	Hits	Search Text	DB	Time stamp
–	3169	semiconductor and plasma and (recycle or recycling or re$1use or circulat$3)	USPAT	2003/12/03 14:10
–	110	(semiconductor and plasma and (recycle or recycling or re$1use or circulat$3)) and SiF?sub.4	USPAT	2003/05/14 15:51
–	596	semiconductor and plasma and (recycle or recycling or re$1use)	USPAT	2003/05/14 15:59
–	535	(semiconductor and plasma and (recycle or recycling or re$1use)) and (monitor$3 or analyz$3 or control$4)	USPAT	2003/05/14 16:09
–	511	((semiconductor and plasma and (recycle or recycling or re$1use)) and (monitor$3 or analyz$3 or control$4)) and @ay<=2000	USPAT	2003/05/14 16:12
–	431	(((semiconductor and plasma and (recycle or recycling or re$1use)) and (monitor$3 or analyz$3 or control$4)) and @ay<=2000) and flow	USPAT	2003/05/14 15:57
–	175	((((semiconductor and plasma and (recycle or recycling or re$1use)) and (monitor$3 or analyz$3 or control$4)) and @ay<=2000) and flow) and ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)	USPAT	2003/05/14 17:45
–	51	semiconductor and (plasma same (recycle or recycling or re$1use))	USPAT	2003/05/14 16:05
–	735	semiconductor and plasma and ((gas or plasma) same (recycle or recycling recycled or recover or recovering or recovered or re$1use))	USPAT	2003/05/14 16:09
–	684	(semiconductor and plasma and ((gas or plasma) same (recycle or recycling recycled or recover or recovering or recovered or re$1use))) not (semiconductor and (plasma same (recycle or recycling or re$1use)))	USPAT	2003/05/14 16:09
–	603	((semiconductor and plasma and ((gas or plasma) same (recycle or recycling recycled or recover or recovering or recovered or re$1use))) not (semiconductor and (plasma same (recycle or recycling or re$1use)))) and (monitor$3 or analyz$3 or control$4)	USPAT	2003/05/14 16:10
–	548	(((semiconductor and plasma and ((gas or plasma) same (recycle or recycling recycled or recover or recovering or recovered or re$1use))) not (semiconductor and (plasma same (recycle or recycling or re$1use)))) and (monitor$3 or analyz$3 or control$4)) and @ay<=2000	USPAT	2003/05/14 16:14
–	248	((((semiconductor and plasma and ((gas or plasma) same (recycle or recycling recycled or recover or recovering or recovered or re$1use))) not (semiconductor and (plasma same (recycle or recycling or re$1use)))) and (monitor$3 or analyz$3 or control$4)) and @ay<=2000) and ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)	USPAT	2003/05/14 16:44

-	211	(((((semiconductor and plasma and ((gas or plasma) same (recycle or recycling recycled or recover or recovering or recovered or re$1use))) not (semiconductor and (plasma same (recycle or recycling or re$1use)))) and (monitor$3 or analyz$3 or control$4)) and @ay<=2000) and ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)) and @py<=2001	USPAT	2003/05/14 16:44
-	165	((((((semiconductor and plasma and ((gas or plasma) same (recycle or recycling recycled or recover or recovering or recovered or re$1use))) not (semiconductor and (plasma same (recycle or recycling or re$1use)))) and (monitor$3 or analyz$3 or control$4)) and @ay<=2000) and ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)) and @py<=2001) and (etch or etching)	USPAT	2003/05/14 17:44
~	4659	plasma with (monitor or monitoring or analyze or analyzing or monitored)	USPAT	2003/05/14 17:45
-	801	(plasma with (monitor or monitoring or analyze or analyzing or monitored) and ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)	USPAT	2003/05/14 17:45
-	552	((plasma with (monitor or monitoring or analyze or analyzing or monitored)) and ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)) and (etch or etching)	USPAT	2003/05/14 17:47
~	298	(((plasma with (monitor or monitoring or analyze or analyzing or monitored)) and ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)) and (etch or etching)) and ((flow adj rate) or sccm)	USPAT	2003/05/15 08:49
-	287	((((plasma with (monitor or monitoring or analyze or analyzing or monitored)) and ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)) and (etch or etching)) and ((flow adj rate) or sccm)) not ((((((semiconductor and plasma and ((gas or plasma) same (recycle or recycling recycled or recover or recovering or recovered or re$1use))) not (semiconductor and (plasma same (recycle or recycling or re$1use)))) and (monitor$3 or analyz$3 or control$4)) and @ay<=2000) and ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)) and @py<=2001) and (etch or etching))	USPAT	2003/05/14 17:55
-	298	(((plasma with (monitor or monitoring or analyze or analyzing or monitored)) and ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)) and (etch or etching)) and ((flow adj rate) or sccm)	USPAT	2003/05/15 08:51
-	192	((((plasma with (monitor or monitoring or analyze or analyzing or monitored)) and ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)) and (etch or etching)) and ((flow adj rate) or sccm)) and @py<=2000	USPAT	2003/05/15 09:39
-	1	5347460.pn.	USPAT	2003/05/15 09:32
-	2	("6081334" | "6406924").PN.	USPAT	2003/05/15 09:39

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